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				U.S. PATENT DOCUMENTS			·		
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V	\$	6,613,658	09/02/2003	M. KOYAMA, et al.	438	591			
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1 V	AW	C. S. KANG, et al., A	oplied Physics	Letters, vol. 81, no. 14, pages 2593-259 0xNy GATE DIELECTRICS", September	5, "BONDI		S AND EL	ECTRICAL	
V- V	AX	M. R. VISOKAY, et al., Applied Physics Letters, vol. 80, no. 17, pages 3183-3185, "APPLICATION OF HISION AS A GATE DIELECTRIC MATERIAL", April 29, 2002							
<u>-</u>	<u> </u>	A KANEKO et al. E	xtended Abstr	acts of the 2002 International Conference	e on Solid S	State Devic	es and Ma	aterials,	
V <sub>m</sub> V	AY	A. KANEKO, et al., Extended Abstracts of the 2002 International Conference on Solid State Devices and Materials, pages 742-743, "PLASMA NITRIDATION TECHNIQUE FOR THE FORMATION OF THERMALLY STABLE Hf-SILICATE GATE DIELECTRIC WITH CONTROLLED NITROGEN PROFILE", 2002							
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